



DOCKET NO. 34261-8500

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Howard Ge, et al.

Serial No.: 10/680,960

Filed: October 7, 2003

For: PHOTORESIST COATING PROCESS
FOR MICROLITHOGRAPHY

Patent Examiner: Chacko Davis, Daborah

Group Art Unit: 1756

Confirmation No.: 6075

September 19, 2006

Costa Mesa, California 92626

INFORMATION DISCLOSURE STATEMENT

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Applicant hereby cites one (1) article for consideration by the Patent and Trademark Office in regard to the claimed invention on the attached form PTO-1449. By this notice the applicant requests that the Patent and Trademark Office make of record the document listed. No representation is made that more pertinent material is not available or should not be considered by the Examiner. It is expected that the Patent and Trademark Office will independently conduct a complete search of appropriate prior art. Furthermore, no admission is being made that this document is prior art, and applicant reserves the right to challenge any such conclusion.

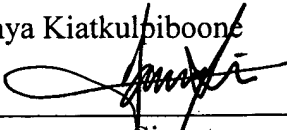
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If there are any questions with regards to the submission, the undersigned attorney can be contacted at the listed phone number.

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class mail in an envelope addressed to Mail Stop Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on September 19, 2006.

By: Tanya Kiatkulpiboone

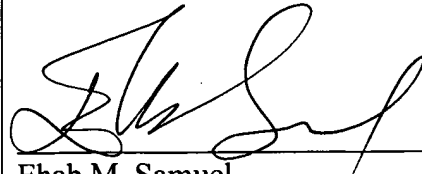


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Dated: September 19, 2006

Very truly yours,

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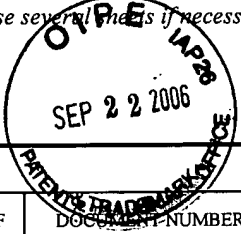
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| INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i> | | | | Docket Number (Optional) | | Application Number | |
| | | | | 34261-8500 | | 10/680,960 | |
| | | | | Applicant(s) Howard Ge, et al. | | | |
| | | | | Filing Date | | Group Art Unit | |
| | | | | 10/07/2003 | | 1756 | |



| U. S. PATENT DOCUMENTS | | | | | | | |
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| EXAMINER INITIAL | REF | DOCUMENT NUMBER | DATE | NAME | CLASS | SUBCLASS | FILING DATE IF APPROPRIATE |
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| U.S. PATENT APPLICATION PUBLICATIONS | | | | | | | |
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| FOREIGN PATENT DOCUMENTS | | | | | | | | |
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| | | | | | | | YES | NO |
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| OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i> | | |
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| | | Corrosion Testing Laboratories, Inc. "Corrosion of Stainless Steel Handrail Caused by Fabrication Process." ©1995-2006. Pages 1-6. Article may be found at Web Site URL: http://www.corrosionlab.com/Failure-Analysis-Studies/29073.corrosion.304ss-handrail.htm |
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